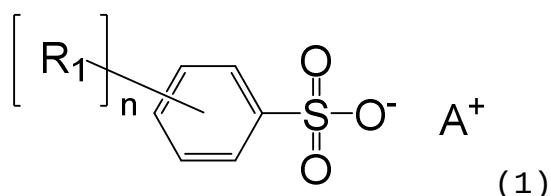


TITLE OF INVENTION: BENZENESULFONIC ACID SALT COMPOUND
FOR FORMING ORGANIC FILM, COMPOSITION FOR FORMING
ORGANIC FILM, METHOD FOR FORMING ORGANIC FILM, AND
PATTERNING PROCESS

ABSTRACT

A composition for forming an organic film, containing: a resin and/or compound (A); a benzenesulfonic acid salt compound (B) represented by the following formula (1), an anion moiety in the formula (1) having a molecular weight of 200 or more, and the compound (B) not containing a perfluoroalkyl group; and a solvent (C). This can provide a composition for forming an organic film possible to form a film with coating properties, coating defects, film-formability, and filling property results, when used as an organic underlayer film for a multilayer resist, that is also useful as a photoresist material, and that contains a benzenesulfonic acid salt that is not a perfluoroalkyl compound (PFAS); a patterning process using the composition; and a compound suitable for the composition.



[FIG 1(A) to 1(F)]